L Number	Hits	Search Text	DB	Time stamp
1	11	((word adj line) wordline) same (nitride with (cap mask))	USPAT;	2004/07/19 14:45
	_ 	same (etch\$6 with ("ccl.sub.4" "cl.sub.2" (carbon adj	US-PGPUB	
	_	tetrachloride) chlorine))	LICOAT	2004/07/40 44:50
2	8	((word adj line) wordline) same (nitride with spacer with	USPAT;	2004/07/19 14:50
		(teos silane))	US-PGPUB	2004/07/40 44-52
3	98	bpsg same (etch\$6 with ("c.sub.4 f.sub.8" "c.sub.2 f.sub.6"	USPAT;	2004/07/19 14:52
	20	"c.sub.3 f.sub.8"))	US-PGPUB	2004/07/40 44-52
4	39	bpsg with (etch\$6 with ("c.sub.4 f.sub.8" "c.sub.2 f.sub.6"	USPAT; US-PGPUB	2004/07/19 14:52
-		"c.sub.3 f.sub.8"))		2004/07/19 14:59
5	1	(cmp (chemical\$4 near mechanical\$4)) with (silicon	USPAT; US-PGPUB	2004/07/19 14.59
ا ر ا	8	polysilicon) with (hard adj pad) (cmp (chemical\$4 near mechanical\$4)) same (silicon	USPAT;	2004/07/19 14:59
6	6	comp (chemicals rhear mechanicals r)) same (sincom polysilicon) same (hard adj pad)	US-PGPUB	2007/07/13 14.33
	2	6436834.pn. 6468910.pn.	USPAT;	2004/07/15 15:50
-		очэовэч.рн. очовэто.рн. 	US-PGPUB	2004/07/13 13.30
_	1	(cmp (chemical\$4 near mechanical\$4)) and (hclo	EPO; JPO;	2004/07/16 17:11
-	1	"hclo.sub.3" hclo3 "hclo.sub.4" hclo4 "hbro.sub.3" hbro3	DERWENT;	2001/07/1017.11
		"hio.sub.3" hio3 "hio.sub.4" hio4)	IBM_TDB	
	9	(cmp (chemical\$4 near mechanical\$4)) same (hclo	USPAT;	2004/07/16 17:06
į į		"hclo.sub.3" hclo3 "hclo.sub.4" hclo4 "hbro.sub.3" hbro3	US-PGPUB	
		"hio.sub.3" hio3 "hio.sub.4" hio4)	33.3.3.	
_	1	5225034.pn.	USPAT;	2004/07/15 16:10
	_		US-PGPUB	
-	7	("3948703" "4305779" "4395302" "4632727"	USPAT	2004/07/15 16:11
	_	"4944836" "4956313" "5084071").PN.		
-	100	5225034.URPN.	USPAT	2004/07/15 16:13
-	176	(cmp (chemical\$4 near mechanical\$4)) same (hocl	USPAT;	2004/07/19 10:35
		(perchloric adj acid) (hypochlorous adj acid) hypochlorite	US-PGPUB	
		(periodic adj acid) (perbromic adj acid) (chloric adj acid)		
		(bromic adj acid) (iodic adj acid))		
-	31	(cmp (chemical\$4 near mechanical\$4)) and (hocl (perchloric	EPO; JPO;	2004/07/16 17:16
		adj acid) (hypochlorous adj acid) hypochlorite (periodic adj	DERWENT;	
		acid) (perbromic adj acid) (chloric adj acid) (bromic adj	IBM_TDB	
		acid) (iodic adj acid))	LICDAT	2004/07/40 44:27
-	3736	((word adj line) wordline) and ((cmp (chemical\$4 near	USPAT; US-PGPUB	2004/07/19 14:37
	2044	mechanical\$4)) same (silicon polysilicon))	USPAT;	2004/07/16 17:39
-	2941	((word adj line) wordline) and ((cmp (chemical\$4 near mechanical\$4)) same (silicon polysilicon) same (spacer	US-PGPUB	2004/07/10 17.59
		contact hole opening nitride))	05-10100	
_	1069	((word adj line) wordline) and ((cmp (chemical\$4 near	USPAT;	2004/07/16 17:40
-	1009	mechanical\$4)) same (silicon polysilicon) same (spacer	US-PGPUB	200 1, 07, 10 17, 10
		nitride) same (contact hole opening))	35 . 3. 35	
_	543	((word adj line) wordline) and ((cmp (chemical\$4 near	USPAT;	2004/07/16 17:43
	5.5	mechanical\$4)) same (silicon polysilicon) same (spacer	US-PGPUB	, ,
		nitride) same ((contact hole opening) with (interlayer		
		dielectric bpsg teos fsg psg usg oxide ild)))	-	
-	1	((cmp (chemical\$4 near mechanical\$4)) same (hocl	USPAT;	2004/07/19 14:57
		(perchloric adj acid) (hypochlorous adj acid) hypochlorite	US-PGPUB	
		(periodic adj acid) (perbromic adj acid) (chloric adj acid)		
		(bromic adj acid) (iodic adj acid))) and (((word adj line)		
		wordline) and ((cmp (chemical\$4 near mechanical\$4)) same		
		(silicon polysilicon)))		2004/07/10 07 55
-	98	((word adj line) wordline) same ((cmp (chemical\$4 near	USPAT;	2004/07/19 07:52
1		mechanical\$4)) same (silicon polysilicon) same (spacer	US-PGPUB	
		nitride) same ((contact hole opening) with (interlayer		
	_	dielectric bpsg teos fsg psg usg oxide ild)))	LICDAT	2004/07/10 00:07
-	2	(cmp (chemical\$4 near mechanical\$4)) same (hocl	USPAT; US-PGPUB	2004/07/19 09:07
		(perchloric adj acid) (hypochlorous adj acid) hypochlorite	U3-PUPUB	
		(periodic adj acid) (perbromic adj acid) (chloric adj acid)]
		(bromic adj acid) (iodic adj acid)) same (bpsg teos fsg psg usg polysilicon "poly-si" polycrystalline poly)		
L	L	Lasa horizering horizer horizer israiling horiz	<u> </u>	L

-	30	(cmp (chemical\$4 near mechanical\$4)) same ("hno.sub.3"	USPAT;	2004/07/19 10:33
		(nitric adj acid)) same (bpsg teos fsg psg usg polysilicon	US-PGPUB	
		"poly-si" polycrystalline poly)		
-	5921	438/637.ccls. 438/675.ccls. 438/684.ccls. 438/692.ccls.	USPAT;	2004/07/19 10:35
		438/693.ccls. 252/79.1.ccls. 252/79.2.ccls.	US-PGPUB	
-	70	(438/637.ccls. 438/675.ccls. 438/684.ccls. 438/692.ccls.	USPAT;	2004/07/19 10:36
		438/693.ccls. 252/79.1.ccls. 252/79.2.ccls.) and ((cmp	US-PGPUB	
		(chemical\$4 near mechanical\$4)) same (hocl (perchloric adj		
		acid) (hypochlorous adj acid) hypochlorite (periodic adj acid)		
		(perbromic adj acid) (chloric adj acid) (bromic adj acid)	ĺ	
		(iodic adj acid)))		